

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	10665	((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:50
L2	0	((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint near3 head	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:50
L3	56	((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and print near3 head	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:52
L4	5	3 and templat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:51
L5	19	((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint near9 templat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:53
L6	216017	((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint nand templat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:53
L7	24	((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint and templat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 11:58
L8	24	radiat\$3 near source and imprint near2 ((device or unit) or head) near6 templat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:01
L9	33	radiat\$3 near source and imprint near2 ((device or unit) or head) and film near6 substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:09
L10	9	radiat\$3 near source and plurality near2 ((regions or patterns) near6 (film near4 substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:14

L11	11120	(detect\$3 or measur\$3) near15 (film near4 substrate) plurality near2 ((regions or patterns) near6 (film near4 substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:15
L12	56	(detect\$3 or measur\$3) near15 (film near4 substrate) and plurality near2 ((regions or patterns) near6 (film near4 substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:15
L13	136	(detect\$3 or measur\$3) near15 (film near4 substrate) and plurality near2 ((regions or patterns) near6 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:16
L14	40	13 and defect	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:21
L15	0	14 and align\$3 near3 error	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:16
L16	0	13 and align\$3 near3 error	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:16
L17	53	13 and align\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:16
L18	19	14 and align\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:16
L19	19	14 and error	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:17
L20	13	18 and 19	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:17

L21	4	13 and measur\$3 near9 defect	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:23
L22	1	13 and compar\$3 near9 defect	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:26
L23	3	13 and ((compar\$3 or calculat\$3) or determin\$3) near6 defect	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:27
L24	56	13 and ((compar\$3 or calculat\$3) or determin\$3) and (defect or error)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:36
L25	2	substrate near defect and templat\$3 near defect	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:28
L26	1086	356/237.1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:37
L27	0	13 and 26	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:37
L28	855	"356"/\$.ccls. and 26	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:37
L29	10	"356"/\$.ccls. and 13	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/03 12:37

AT-NO: JP402159012A
DOCUMENT-IDENTIFIER: JP 02159012 A
TITLE: MASK SUBSTRATE
PUBN-DATE: June 19, 1990

INVENTOR-INFORMATION:
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APPL-NO: JP63314279
APPL-DATE: December 12, 1988

INT-CL (IPC): H01L021/027, G03F001/08
US-CL-CURRENT: 257/797

ABSTRACT:

PURPOSE: To detect any defect of a finner reticle by forming a plurality of light shielding films on a plurality of regions on a surface of a transparent substrate as a mask substrate for use in checking the reticle.

CONSTITUTION: A mask substrate 1 includes a Cr light shielding film 1b, an Al light shielding film 1c, and a Cu light shielding film 1d formed by deposition with a plurality of metals on a plurality of regions of a surface of a transparent substrate 1a. In a surface inspection device, any defect is detected by comparing shielding film patterns formed on the mask substrate 1 surface. The shielding film pattern in this case is formed of a normal reticle pattern 2a and a defective reticle pattern 2b of a reticle 2. In

case of a pin
hole as illustrated in the drawings, a pin hole through the Al
shielding film
1c is great 0.3 μ m or more in its diameter than a pin hole in the
Cr
shielding film 1b, so that any pin hole not found in the Cr shielding
film 1b
can be found in the Al shielding film 10.

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